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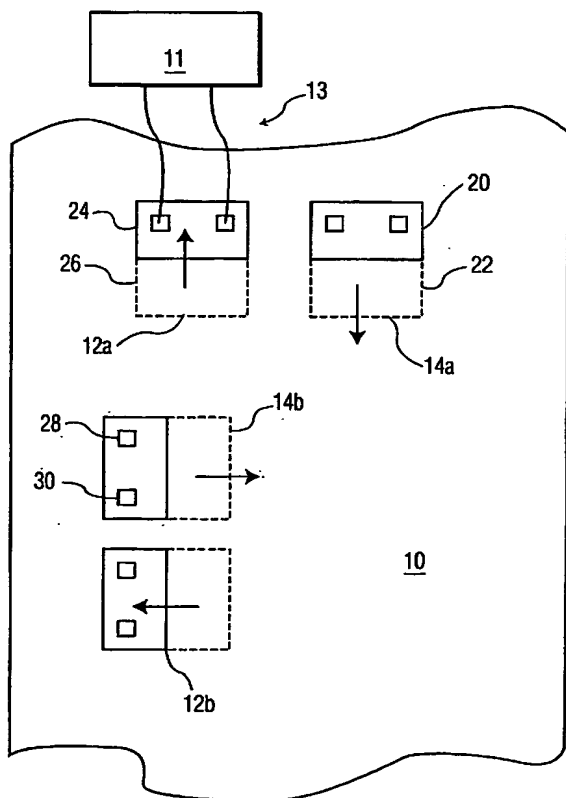
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(54) Title: OFFSET DEPENDENT RESISTOR FOR MEASURING MISALIGNMENT OF STITCHED MASKS



(57) Abstract: A system and method for identifying misalignments in an overlapping region of a stitched circuit in an integrated circuit fabrication process. The method comprises: creating a first circuit using a reference mask, wherein first circuit includes a first part of an offset dependent resistor structure in the overlapping region; creating a second circuit using a secondary mask, wherein the second circuit includes a second part of the offset dependent resistor structure in the overlapping region, wherein the offset dependent resistor structure includes a plurality of nubs that interconnect the first part and the second part of the offset dependent resistor structure; measuring a resistance across the offset dependent resistor structure; and determining an amount of misalignment based on the measured resistance.



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